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## **Supporting Information**

## Fabrication of high performance memristor device by metallization of Ag<sup>+</sup> inside a solution processed Li<sub>5</sub>AlO<sub>4</sub> thin film

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Figure S1. Cross-sectional SEM image for a) p<sup>+</sup>-Si/Ag(Ag<sup>+</sup>)-Al<sub>2</sub>O<sub>3</sub>.



**Figure S2.** a) HR-SEM image of the  $Ag(Ag^+)-Al_2O_3$  thin film. b) EDX studies. c) Color mapping analysis of  $Ag(Ag^+)-Al_2O_3$ . d)  $Ag(Ag^+)-Al_2O_3$  thin film image captured by TEM. e) Ag (NPs) particle size distribution inside an  $Al_2O_3$  matrix as seen in a TEM image.



**Figure S3.** Current & Voltage curve of device  $p^+$ -Si/Ag(Ag<sup>+</sup>)-Al<sub>2</sub>O<sub>3</sub>/Ag with concentrations of a)100 mM b) 200 mM and, c) 500 mM of Li<sub>5</sub>AlO<sub>4</sub> ion conducting dielectric.



Figure S4. Current & Voltage curve of device  $p^+$ -Si/Ag(Ag<sup>+</sup>)-Al<sub>2</sub>O<sub>3</sub>/Ag with top electrode area of a) 0.18 mm<sup>2</sup> b) 0.71 mm<sup>2</sup> and, c) 1.60 mm<sup>2</sup>. Current vs. Voltage curve of  $p^+$ -Si/Ag(Ag<sup>+</sup>)-Al<sub>2</sub>O<sub>3</sub>/Ag on a semi-logarithmic scale for continuous measurement with top electrode area d) 0.18 mm<sup>2</sup> and e) 0.71 mm<sup>2</sup>.



Figure S5. a) Current vs. Voltage curve of p<sup>+</sup>-Si/Ag(Ag<sup>+</sup>)-Al<sub>2</sub>O<sub>3</sub>/Au on a semi-logarithmic scale,
b) Endurance property of p<sup>+</sup>-Si/Ag(Ag<sup>+</sup>)-Al<sub>2</sub>O<sub>3</sub>/Au for 20 cycles of continuous measurement.



**Figure S6.** a) Measured device-to-device variation of switching voltage distribution. b) Measured device-to-device variation of HRS and LRS distributions.



Figure S7. Pulse switching endurance for two resistance states of a)  $p^+$ -Si/ (Ag/Ag<sup>+</sup>)-Al<sub>2</sub>O<sub>3</sub>/Ag, and b)  $p^+$ -Si/Ag(Ag<sup>+</sup>)-Al<sub>2</sub>O<sub>3</sub>/Ag, respectively.



**Figure S8**. The statistic histograms of set and reset voltage over 100 consecutive cycles of  $p^+$ -Si/(Ag/Ag^+)-Al<sub>2</sub>O<sub>3</sub>/Ag. Lines are obtained by fitting to the Gaussian distribution.



Figure S9. Current vs. Voltage curve for the device  $p^+-Si/Ag(Ag^+)-Al_2O_3/Ag$  under hot air treatment.